

035576/275

**DELPHION****Select****RESEARCH****PRODUCTS****INSIDE DELPHION****Log Out** **Work Files** **Saved Searches**

My Account

Search: Quick/Number Boolean Advanced Der

**The Delphion Integrated View**Buy Now: ☒ PDF | [More choices](#)Tools: Add to Work File: [Create new Work](#)View: INPADOC | Jump to: [Top](#) ☒ Go to: [Derwent](#)☒ Email

🔍 Title: **JP2000345041A2: COMPOSITION FOR FORMING FILM, PRODUCTIC  
COMPOSITION FOR FORMING FILM, AND MATERIAL FOR FORMING  
INSULATION FILM**

🔍 Derwent Title: Composition for film formation for production of semiconductors,  
comprises a product of hydrolysis and condensation obtained by  
hydrolyzing and condensing organosilicon compound(s) [\[Derwent Record\]](#)

🔍 Country: JP Japan

🔍 Kind: A2 Document Laid open to Public inspection i

🔍 Inventor: **NISHIKAWA MICHINORI;  
TSUNODA MAYUMI;  
INOUE YASUTAKE;  
YAMADA KINJI;**

🔍 Assignee: **JSR CORP**  
[News, Profiles, Stocks and More about this company](#)

🔍 Published / Filed: 2000-12-12 / 1999-06-04

🔍 Application  
Number: **JP1999000158674**

🔍 IPC Code: **C08L 83/04; C08K 5/06; H01L 21/312; H01L 21/316;**🔍 Priority Number: 1999-06-04 **JP1999000158674**

🔍 Abstract: **PROBLEM TO BE SOLVED:** To obtain a composition having improved storage stability and giving a film improved in uniformity, permittivity, and leak current characteristics by selecting a composition containing a hydrolyzate of a silane compound or a condensate of the hydrolyzate and having a specified propylene glycol content.

**SOLUTION:** This composition contains at least either of a hydrolyzate and/or a condensate selected from a compound of formula I and a compound of formula II and a solvent of formula III of a purity of 99% (as measured by gas chromatography) and has a propylene glycol content of 10,000 ppm or below. In the formula, R1 is H, F, or a monovalent organic group; R2 to R6 are each a monovalent organic group; a, b, and c are each 0-2; R7 is O or - (CH2)n-; in formula II, n is 1-6; d is 0 or 1; R8 and R9 are each a monovalent organic group selected from H, a 1-4C alkyl, and CH3CO-; and e is 1-2. The composition desirably has an iron content and a sodium content each of which is 15 ppb or below and may contain a  $\beta$ -diketone, a compound having a polyalkylene oxide structure, or the like.

COPYRIGHT: (C)2000,JPO

🔍 INPADOC None

Buy Now: [Family Legal Status Report](#)






Legal Status:

Designated

BE DE FR GB IT NL

Country:

Family:

Buy PDF	Publication	Pub. Date	Filed	Title
	<a href="#">US6376634</a>	2002-04-23	2000-06-02	Composition for film formation and ma insulating film formation
	<a href="#">JP2001164113A2</a>	2001-06-19	1999-12-13	COMPOSITION FOR FILM FORMATI MATERIAL FOR FORMING INSULAT
	<a href="#">JP2000345041A2</a>	2000-12-12	1999-06-04	COMPOSITION FOR FORMING FILM PRODUCTION OF COMPOSITION FO FORMING FILM, AND MATERIAL FO FORMING INSULATION FILM
	<a href="#">EP1058274B1</a>	2005-07-27	2000-05-31	Composition for film formation and ma insulating film formation
	<a href="#">EP1058274A1</a>	2000-12-06	2000-05-31	Composition for film formation and ma insulating film formation
	<a href="#">DE60021476C0</a>	2005-09-01	2000-05-31	Beschichtungszusammensetzung für c Filmherstellung und Material für isolier Schichten
6 family members shown above				

Other Abstract  
Info:CHEMABS 134(03)030163H [DERABS C2001-204180](#)

Nominate this for the Gallery...


**THOMSON**  


Copyright © 1997-2005 The Tho

[Subscriptions](#) | [Web Seminars](#) | [Privacy](#) | [Terms & Conditions](#) | [Site Map](#) | [Contact U](#)

BEST AVAILABLE COPY